

Inventor: **H. Daniel Dulman**

Title: **Radiation Patterning Tools, and Methods of Forming Radiation
Patterning Tools**

Assignee: **Micron Technology, Inc.**

RECEIVED

Serial No.: **10/072,440**

FEB 10 2004

Filed: **February 5, 2002 [RCE Filed Herewith]**

OFFICE OF PETITIONS

INFORMATION DISCLOSURE STATEMENT

PURSUANT TO 37 C.F.R. §§ 1.56, 1.97 AND 1.98

In compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, the Examiner's attention is directed to the references listed on the attached Form PTO-1449 and copies of which are attached. No admission is made regarding whether all the submitted references are prior art.

Citation of these references is respectfully requested.

Respectfully submitted,

Date: 2/9/04

Attorney:


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U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE				ATTY. DOCKET NO. MI22-1829	SERIAL NO. 10/072,440
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT H. Daniel Dulman	
				FILING DATE Feb. 5, 2002 [RCE Filed Herewith]	GROUP 1756

U.S. PATENT DOCUMENTS

*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	5,629,113	05/97	Watanabe			
	AB	6,007,324	12/99	Tzu et al.	RECEIVED		
	AC	5,384,219	01/95	Dao et al.	FEB 10 2004		
	AD	5,300,379	04/94	Dao et al.	OFFICE OF PETITIONS		
	AE	5,897,975	04/99	Ahn et al.			
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AL	US 03/ 02288	01/03	PCT Search Report				
	AM	0 395 425 A2/A3	04/90	EPO				
	AN	0 583,942 A2	08/93	EPO				
	AO							
	AP							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

	AQ		Cui, Z. et al., "Partial Rim: A New Design of Rim Phase Shift Mask for Submicron Contact Holes", SPIE				
			Vol. 2440, Feb. 1995, pp. 541-549.				
	AR						
	AS						

EXAMINER

DATE CONSIDERED

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.